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Attorney Docket no: SEL 246

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Koichiro TANAKA)
)
Serial No.: 09/812,529)
)
Filed: March 20, 2001)
)
For: Method of Manufacturing A Semiconductor)
Device)
)
Examiner: R. Booth)
)
Art Unit: 2812)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: the Assistant Commissioner for Patents, Washington, D.C. 20231 on August 28, 2002 9/16/02
(Date of Deposit)

Rachelle Hammerquist 8-28-02
Name of applicant, assignee, or Registered Rep. Signature Date

Commissioner for Patents
Washington D.C. 20231

AMENDMENT A

In response to the Office Action of March 28, 2002, a two month extension of time being separately requested, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

1 (Amended). A method of manufacturing a semiconductor device, comprising:
forming an amorphous semiconductor film over a substrate;
irradiating the amorphous semiconductor film with a first laser beam to form a first crystalline semiconductor film; and
irradiating the first crystalline semiconductor film with a second laser beam to form a second crystalline semiconductor film,